

Notic of Referenc s Cited	Application/Control No. 10/066,627	Applicant(s)/Patent Under Reexamination KATO ET AL.	
	Examiner Maria Guerrero	Art Unit 2822	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6,333,547	12-2001	Tanaka et al.	257/649
	C	US-6,268,299	07-2001	Jammy et al.	438/791
	D	US-6,284,583	09-2001	Saida et al.	438/216
	E	US-5,482,739	01-1996	Hey et al.	427/255.39
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	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	R.C. Taylor et al. "LPCVD of Silicon Nitride Films From Hexachlorodisilane and Ammonia", 1988, Materials Research Society, Vol. 105, pages 319-324.
	V	Tanaka et al. "Film Properties of Low-k Silicon Nitride Films Formed by Hexachlorodisilane and Ammonia", 2000, Journal of The Electrochemical Society, pages 2284-2289.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.